

Amendments to the Claims:

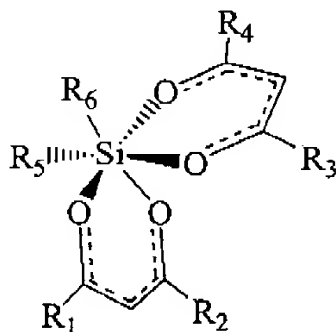
- B²
1. (currently amended) A ~~solvent~~ CVD precursor solution including a solvent component and a hexacoordinated silicon beta-diketonate composition of the formula $R_2Si(\beta\text{-diketonate})_2$ or $(RO)_2Si(\beta\text{-diketonate})_2$, wherein each R is the same as or different from the other R, and each R is independently selected from H, aryl, fluoroaryl, $C_1 - C_{12}$ alkyl, $C_1 - C_{12}$ fluoroalkyl, and $C_1 - C_{12}$ silicon-containing alkyl.
 2. (currently amended) The ~~solvent~~ precursor solution of claim 1, wherein each β -diketonate ligand of the composition may be the same as or different from the other β -diketonate ligand of the composition, and is independently selected from: 2,2,6,6-tetramethyl-3,5-heptanedionate; 1,1,1,2,2,3,3-hepta-fluoro-7,7-dimethyloctane-4,6-dionate; acetylacetonate; trifluoro-acetylacetonate; and hexafluoroacetylacetonate.
 3. (currently amended) The ~~solvent~~ precursor solution of claim 1, wherein each β -diketonate ligand of the composition is 2,2,6,6-tetramethyl-3,5-heptanedionate.
 4. (currently amended) The ~~solvent~~ precursor solution of claim 1, wherein the composition is of the formula $R_2Si(\beta\text{-diketonate})_2$.
 5. (currently amended) The ~~solvent~~ precursor solution of claim 1, wherein the composition is of the formula $(RO)_2Si(\beta\text{-diketonate})_2$.
 6. (currently amended) The ~~solvent~~ precursor solution of claim 1, wherein the composition is of the formula $(t\text{-BuO})_2Si(2,2,6,6\text{-tetramethyl-3,5-heptanedionate})_2$.
 7. (currently amended) The ~~solvent~~ precursor solution of claim 1, wherein the composition is of the formula $(CH_3)_2Si(2,2,6,6\text{-tetramethyl-3,5-heptanedionate})_2$.
 8. (previously canceled)

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cont.

9. (currently amended) The ~~solvent~~ precursor solution of claim 1, wherein said solvent component comprises ~~including~~ a hydrocarbon solvent.

10. (currently amended) The ~~solvent~~ precursor solution of claim 1, wherein said solvent component comprises ~~including~~ octane.

11. (currently amended) A precursor solution for use in chemical vapor deposition, comprising a solvent component and a silicon β -diketonate ~~for use in chemical vapor deposition and~~ of the formula:

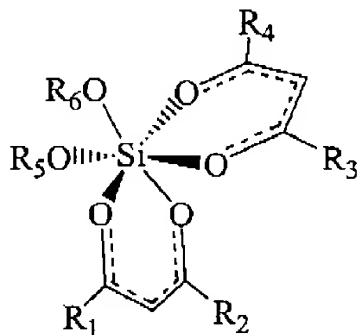


wherein:

R₁, R₂, R₃ and R₄ are the same as or different from one another, and wherein each of such substituents is independently selected from H, aryl, fluoroaryl, C₁ - C₁₂ alkyl, C₁ - C₁₂ fluoroalkyl, and C₁ - C₁₂ silicon-containing alkyl; and

R₅ and R₆ are same as or different from one another, and each is independently selected from H, aryl, fluoroaryl, C₁ - C₁₂ alkyl, C₁ - C₁₂ fluoroalkyl, and C₁ - C₁₂ silicon-containing alkyl.

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cont.
12. (currently amended) A precursor solution for use in chemical vapor deposition, comprising a solvent component and a silicon β -diketonate ~~for use in chemical vapor deposition and~~ of the formula:



wherein:

- R_1 , R_2 , R_3 and R_4 are the same as or different from one another, and wherein each of such substituents is independently selected from H, aryl, fluoroaryl, $C_1 - C_{12}$ alkyl, $C_1 - C_{12}$ fluoroalkyl and $C_1 - C_{12}$ silicon-containing alkyl; and
- R_5 and R_6 are same as or different from one another, and each is independently selected from H, aryl, fluoroaryl, $C_1 - C_{12}$ alkyl, $C_1 - C_{12}$ fluoroalkyl, and $C_1 - C_{12}$ silicon-containing alkyl.

13-34. (previously canceled)

35-38. (currently cancelled)

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39. (new) A novel composition comprising $(t\text{-OBu})_2\text{Si}(\text{thd})_2$.

40. (new) A novel composition comprising $(\text{CH}_3)_2\text{Si}(\text{thd})_2$.